L Number	Hits	Search Text	DB	Time stamp
1	16	UHV same susceptor	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 10:02
3	1	batch same susceptor and UHV	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 10:05
4	93	batch same susceptor and CVD	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 10:06
5	9	batch same susceptor same horizontal$4 and CVD	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 10:19
6	24	(planarty or planetary) same susceptor	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 11:41
12	32	susceptor same (temperature or thermal) near5 (control$4 or monitor$4) same (sensor or thermocouple) and cvd.ti.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 13:54
13	28	susceptor same (temperature or thermal) near5 (control$4 or monitor$4) same (sensor or thermocouple) same vacuum and cvd	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 13:56
14	5	susceptor same (temperature or thermal) near5 (control$4 or monitor$4) same (sensor or thermocouple) same vacuum and cvd and batch	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 13:58
18	1	planetary same susceptor and susceptor same (sensor or thermocouple) and cvd	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 14:00
37	4	deep adj trench same CVD and @py<2001 and UHV	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 15:11
38	2	deep adj trench same CVD same vacuum and @py<2001	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 15:11
39	1	deep adj trench same CVD and @py<2001 and 117/$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 15:13
40	83	deep adj trench same CVD and @py<2001 and 438/$4.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 15:26
41	110	(ald or atomic adj layer adj deposit$4) same Si	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 15:28

42	2	(ald or atomic adj layer adj deposit$4) same Si and UHV	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 15:29
43	29	(ald or atomic adj layer adj deposit$4 or ale) and UHV	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 15:32
73	10	ale and suntola.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 15:42
74	3	(ald or atomic adj layer adj deposit$4 or ale) same UHV	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 15:33
75	3	(ald or atomic adj layer adj epitax$4 or ale) same UHV	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 15:37
76	458	(ald or atomic adj layer adj epitax$4 or ale) same vacuum	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 15:37
-	9	hans.in. and buschbeck.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/02 15:28
-	5	((UHV or ultra adj high adj vacuum) same (CVD or chemical adj vapor adj deposit$4) or UHV$1CVD) same batch and (treat$4 or clean$4) same vacuum	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/25 13:08
-	7	((UHV or ultra adj high adj vacuum) same (CVD or chemical adj vapor adj deposit$4) or UHV$1CVD) same batch	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/25 13:09
-	10	(hydrogen or "h.sub.2") near4 plasma same clean$4 same (ev)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/03 11:04
-	4	(hydrogen or "h.sub.2") near4 plasma same (ev) same (wafer or substrate) same oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/03 11:07
-	48	(hydrogen or "h.sub.2") near4 plasma same (ev) same (wafer or substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/03 11:07
-	21	(hydrogen or "h.sub.2") near4 plasma near20 (ev) same (clean$4 or passivat$4 or oxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/03 11:32
-	24	(hydrogen or "h.sub.2") near4 plasma near10 energy same (clean$4 or passivat$4 or native adj oxide) same (wafer or substrate)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/03 11:42

-	8	(ALD or ale or atomic adj layer adj (epitax$4 or deposit$4)) same (UHV or ultra adj high adj vacuum)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/03 13:25
-	78	(CVD or chemical adj vapor adj deposit$4) and vertical same horizontal same batch	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/03 14:28
-	11	(UHV or ultra adj high adj vacuum near4 (CVD or chemical adj vapor adj deposit$4)) same vertical same horizontal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/03 15:06
-	1	(UHV or ultra adj high adj vacuum near4 (CVD or chemical adj vapor adj deposit$4)) same vertical near5 reactor	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/03 14:40
-	56	(UHV or ultra adj high adj vacuum near4 (CVD or chemical adj vapor adj deposit$4)) and (vacuum near10 (furnace or heater))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/03 15:13
-	2	5755938.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/03 16:09
-	85	temperature near10 control near10 distribution same (reactor or chamber) and (CVD or chemical adj vapor adj deposition)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 10:00